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978-1-107-41088-6 - Materials Research Society Symposium Proceedings: Volume 126:

Advanced Surface Processes for Optoelectronics

Editors: S. L. Bernasek, T. Venkatesan and H. Temkin

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MATERIALS RESEARCH SOCIETY SYMPOSIUM PROCEEDINGS VOLUME 126

Advanced Surface Processes for Optoelectronics

Symposium held April 5-8, 1988, Reno, Nevada, U.S.A.

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Pittsburgh, Pennsylvania

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Cambridge, New York, Melbourne, Madrid, Cape Town,
Singapore, São Paulo, Delhi, Mexico City

Cambridge University Press
32 Avenue of the Americas, New York NY 10013-2473, USA

Published in the United States of America by Cambridge University Press, New York

www.cambridge.org
Information on this title: www.cambridge.org/9781107410886

Materials Research Society
506 Keystone Drive, Warrendale, PA 15086
<http://www.mrs.org>

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First published 1988
First paperback edition 2012

Single article reprints from this publication are available through
University Microfilms Inc., 300 North Zeeb Road, Ann Arbor, MI 48106

CODEN: MRSPDH

ISBN 978-1-107-41088-6 Paperback

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Preface

The field of opto-electronics is advancing at a rapid pace with the discovery of novel material systems as well as new processing ideas. The last decade has seen the maturing of technologies such as ion implantation of opto-electronic materials, energetic-beam processing of surfaces, epitaxy and heteroepitaxy of lattice matched and non-lattice matched systems, and novel growth techniques such as chemical beam epitaxy and energetic-beam assisted growth. The field has further benefited from understanding metal surface reactions to form controlled barriers, and the development of techniques to fabricate sub-micron structures both above and below the surfaces of solids. The aim of this symposium was to bring together the diverse group of researchers involved in these multifaceted fields. We have accomplished a successful beginning at the 1988 MRS Spring Meeting in Reno. We would particularly like to thank all the contributors and referees and would like to acknowledge the following session chairmen: E. Weber, J. Merz, E.H. Lee, S.J. Pearton, C.J. Palmström, E. Yablonovich, and A. Scherer for their stimulating participation.

We would especially like to thank Susan Perzel at Princeton University for her invaluable help in putting this proceedings volume together.

S.L. Bernasek
T. Venkatesan
H. Temkin

June, 1988

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